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ARCADIA



Advanced Readout CMOS Architectures with Depleted Integrated sensor Arrays

First characterization results of ARCADIA FD-MAPS after x-ray irradiation

Coralie Neubüser, T. Corradino, G-F. Dalla Betta, S. Matiazzo, L. Pancheri
on behalf of the ARCADIA collaboration

29/06/2022

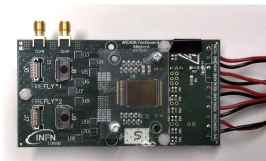
23rd International Workshop on Radiation Imaging Detectors

ARCADIA main demonstrator characterisation

analysis currently ongoing...



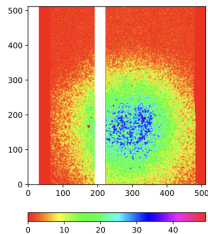
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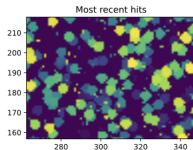
110 nm CMOS CIS technology,
high-resistivity bulk, operated
in full depletion mode

Pixel size = $25 \times 25 \mu\text{m}^2$
Matrix = 512×512
Thickness = $200 \mu\text{m}$

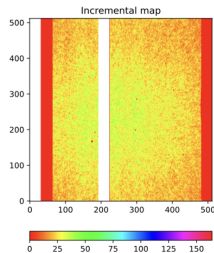
^{241}Am



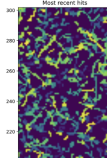
Few events (zoom)



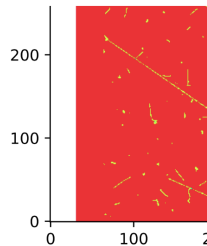
^{90}Sr



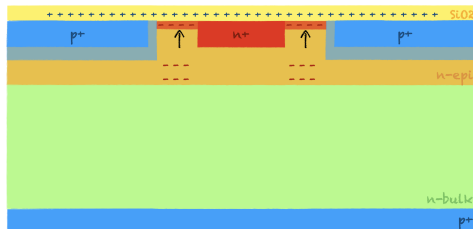
Few events (zoom)



Few cosmic tracks
(Tilted sensor)



...more results are coming soon.



capacitance at nwell is input
capacitance to readout chain
thus impacts noise of chip

- ▶ started investigation of impact of oxide charges on pixel capacitance in 2020 in simulations (different pixel designs for ARCADIA engineering runs)
[1] [C. Neubüser et al., *Sensor design optimization of innovative low-power, large area MAPS for HEP and applied science*, in *Frontiers in Physics* Vol. 9 2021, doi:10.3389/fphy.2021.625401]
- ▶ presented impact of X-ray irradiation on SEED (predecessor of ARCADIA) samples at iWorld 2021
[2] [C. Neubüser et al., *Impact of X-ray induced radiation damage on FD-MAPS of the ARCADIA project*, 2022 JINST 17 C01035]

in the meantime... 2 production runs of ARCADIA FD-MAPS.

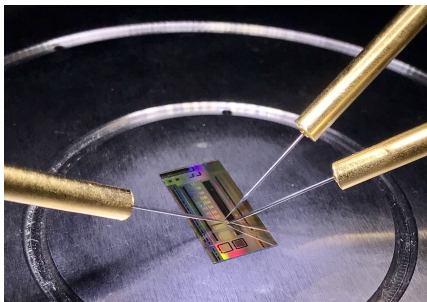
ARCADIA passive pixel matrices

allow electronics independent process validation and tests for pixel design optimizations



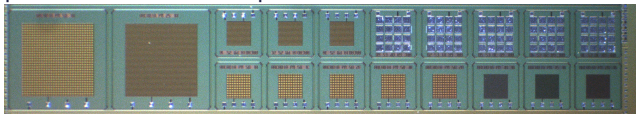
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wafer	wafer type	thickness [μm]
20,22	1	48
3,10	2	100
6,15	3	200



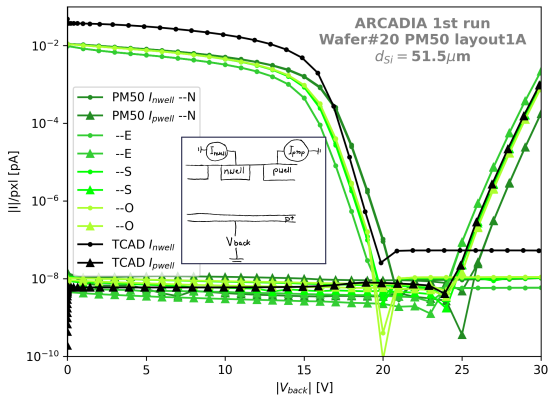
- ▶ two large $1.5 \times 1.5 \text{ mm}^2$ matrices with pixels of 25 and $50 \mu\text{m}$ pitch
- ▶ 3/3/5 small $500 \times 500 \mu\text{m}^2$ matrices with different designs for pixels of 10/25/50 μm pitch
- ▶ each pixel type, one design optimised for low capacitance and one for fast charge collection

picture under microscope:



pitch [μm]	# layouts
50	5
25	3
10	3

IV curves used to match simulation to data per wafer



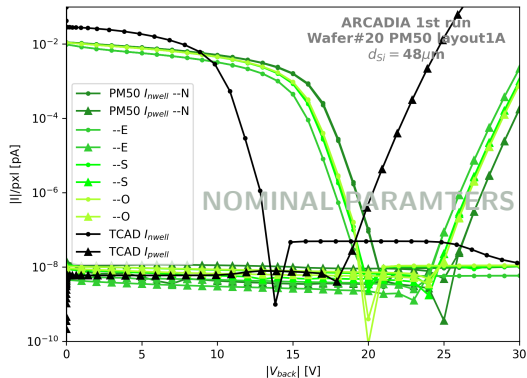
- uncertainties on doping concentrations, thicknesses and implant accuracies taken to reproduce data

variable	uncertainty*
N_{sub}	(42 / 230)%
d_{Si}	(- / 8)%
d_{epi}	(12 / 14)%

*given for 2 main wafer types

- multidimensional parameter space only limited by necessary CPUs for 3D TCAD simulations
- found good matches of the operating voltage range

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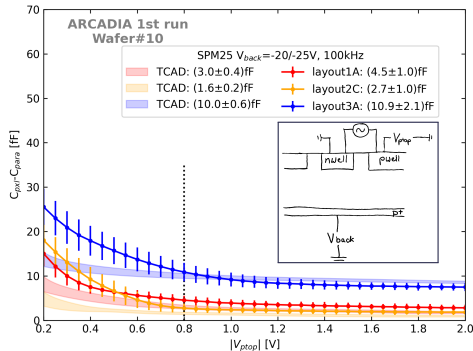
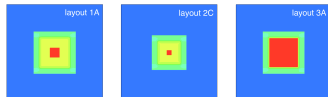
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CV curves for different pixel designs

$25 \times 25 \mu\text{m}^2$ pixels



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- ▶ in simulations observed already at low oxide charge concentrations non-negligible impact on capacitance [1]
- ▶ TCAD simulations include $N_{\text{ox}} = 6.5 \cdot 10^{10} \text{ cm}^{-3}$
- ▶ simulations show too low capacitances, potentially underestimated N_{ox}
- ▶ found oxide charge concentrations with gated diodes on backside of $1-1.5 \times 10^{12} \text{ cm}^{-3}$ [3], but need estimations of frontside

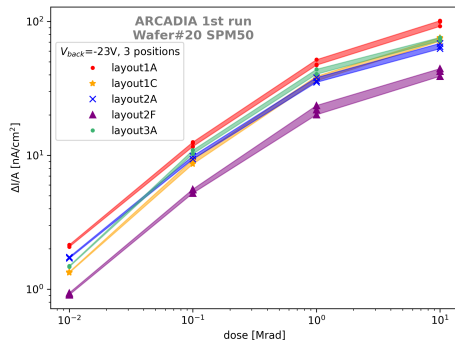
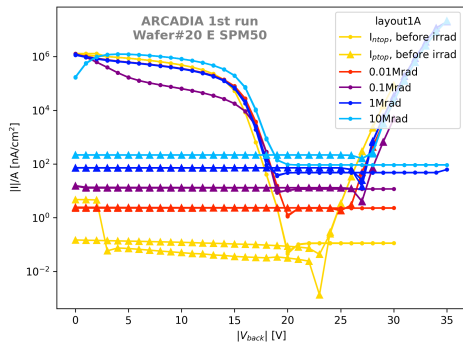
[3] T. Corradino et al., *Design and Characterization of Backside Termination Structures for Thick Fully-Depleted MAPS*, MDPI Sensors doi:10.3390/s21113809

Leakage current after x-ray irradiation

together with Uni Padova irradiation campaign with x-ray tube with a Tungsten anode, up to a dose of 10Mrad



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- ▶ all measurements performed at room temperature
- ▶ after every radiation step, annealing step of 10min@80°C
- ▶ stable operating range
- ▶ non-linear increase of radiation induced leakage currents with possible saturation >1 Mrad

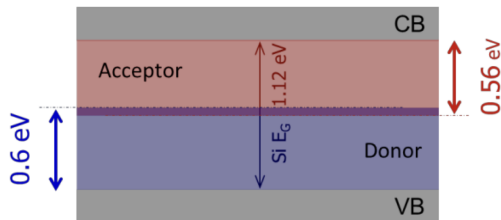
Modelling of surface damage in TCAD

following New Perugia model [6,7]

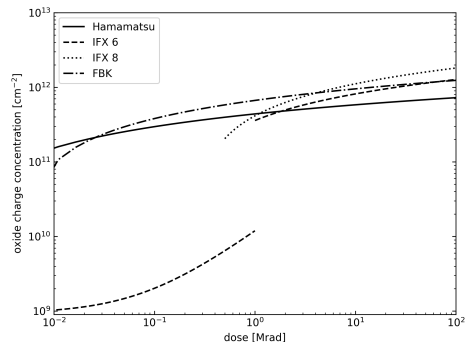


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- ▶ included positive oxide charge, and 1 acceptor + 1 donor trap



- ▶ parametrized on p-type Si from different producers; Hamamatsu, Infineon, FBK
- ▶ data points from 50 krad-100 Mrad



- ▶ oxide charge $(1 \cdot 10^9 - 8 \cdot 10^{10}) \text{ cm}^{-2}$ at 0 dose

[6] AIDA2020 report,

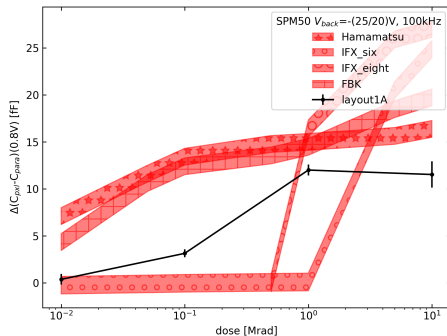
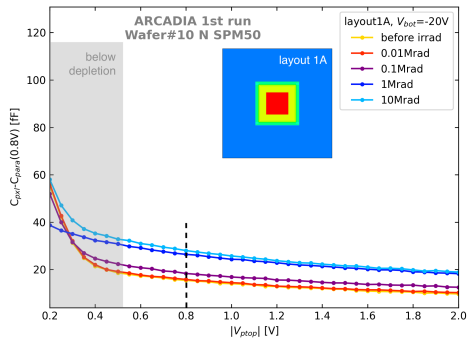
[7] A. Morozzi et al., TCAD Modeling of Surface Radiation Damage Effects: A State-Of-The-Art Review, *Frontiers in Physics* doi:10.3389/fphy.2021.617322

CV curves before/after irradiation

$50 \times 50 \mu\text{m}^2$ pixels



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- ▶ impact of surface damage on capacitance clearly visible
- ▶ capacitance almost doubles after 10Mrad, starting from 15fF before irradiation
- ▶ comparison with simulation: none of the models describes the data over full dose range

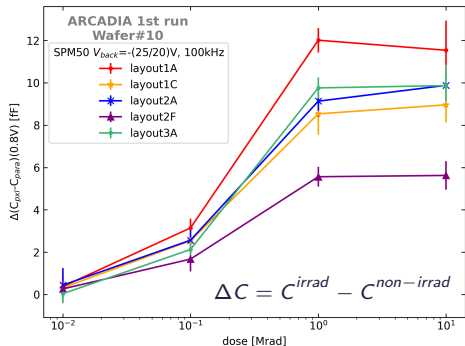
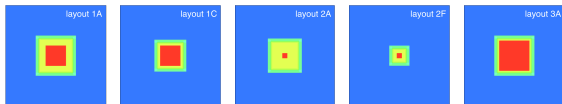
→ included new test-structures in next ARCADIA run to determine trap and oxide charge concentrations for new paramterisation

Capacitance increase for different pixel designs

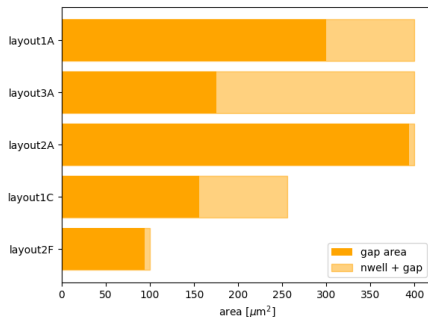
$50 \times 50 \mu\text{m}^2$ pixels



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- ▶ absolute capacitance increase of up to 12 fF/pixel



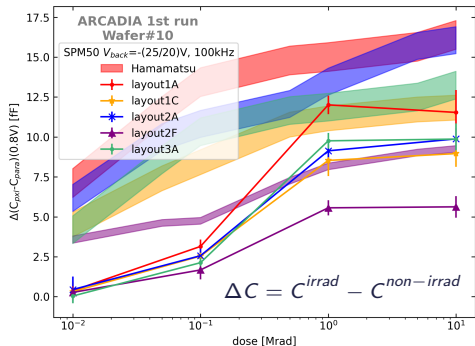
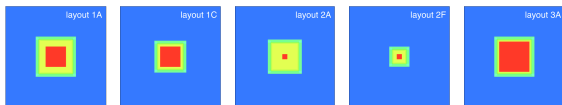
- ▶ layouts differ in collection node size and gap between n and pwell
- ▶ increase of the capacitance is clearly correlated with pwell-free area

Capacitance increase for different pixel designs

$50 \times 50 \mu\text{m}^2$ pixels



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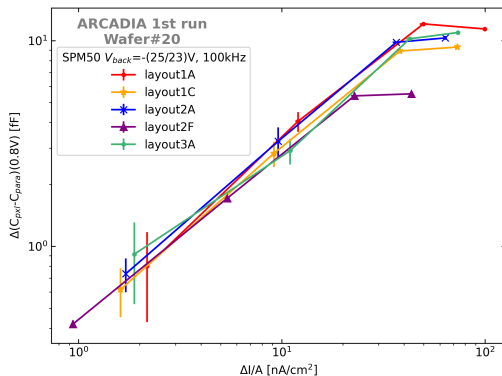
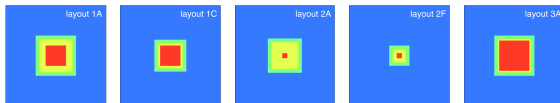
- ▶ Hamamatsu parametrisation predicts earlier and stronger increase of capacitance
- ▶ good reproduction of the impact of the designs on capacitance
- ▶ layout optimised for low capacitance before irradiation, shows smallest impact of surface damage after irradiation

Capacitance-current increase correlation

$50 \times 50 \mu\text{m}^2$ pixels



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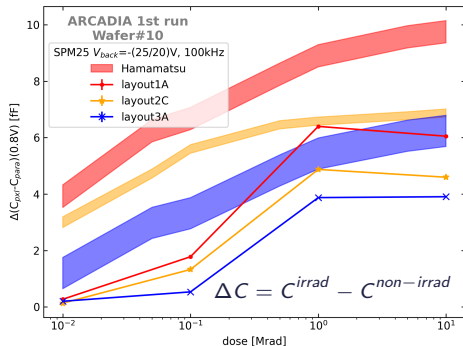
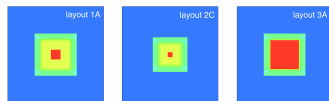
- ▶ clear correlation between capacitance and leakage current increase
- ▶ all layouts show similar relationship, except for saturation in capacitance which is observed at different stages of leakage increase

Capacitance increase for different pixel designs

$25 \times 25 \mu\text{m}^2$ pixels



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- ▶ similar results on matrices with smaller pixel pitch

potentially interesting design of small capacitance (layout 2C):

- ▶ 3 fF/pixel before irradiation
- ▶ smaller increase after irradiation compared to *default* pixel (layout 1A), currently in use in main demonstrator (MD) chip
- ▶ slower charge collection at edges

- ▶ ARCADIA collaboration successfully produced functional sensors in first 2 production runs
- ▶ method to adjust TCAD inputs per wafer established and good agreement with measurements achieved
- ▶ surface damage non-negligible impact on pixel capacitances, main trends of impact of positive oxide charges validated with data
- ▶ radiation damage model needs technology-optimised parametrisation
→ gated diodes and MOS capacitors included in 3rd ARCADIA run for characterisation and parameter determination

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THANK YOU FOR YOUR ATTENTION!

ARCADIA collaboration

INFN - Bologna, Milano, Padova, Perugia, Pavia, TIFPA, Torino



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Many thanks!

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BACKUP

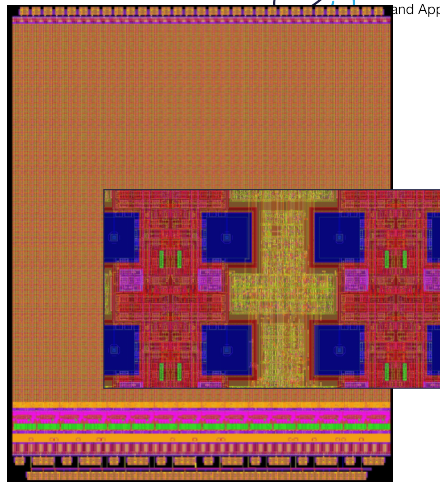
ARCADIA MD1 – specs

trigger-less, and binary readout



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- ▶ matrix core 512×512 pxls of $25 \mu\text{m}$ pitch
- ▶ pixels are $\sim(50/50)\%$ analog/digital
- ▶ sensor diode about 20% of total area
- ▶ clock-less matrix (to minimize power dissipation)
- ▶ pixel regions propagate the output data to the periphery



Manuel Rolo, INFN Torino